IN THE CLAIMS:

Claim 1 (currently amended) A substrate cleaning method for cleaning a substrate using a cleaning liquid comprising at least one selected from ~~the~~ a first group consisting of an aqueous solution of ammonium fluoride[[,]] and a mixture of an aqueous solution of ammonium fluoride and hydrofluoric acid, comprising the steps of:

dipping ~~and~~ the substrate in said cleaning liquid;

cleaning the substrate in said cleaning liquid; and

adding a replenishing liquid comprising at least one selected from ~~the~~ a second group consisting of ~~water,~~ ammonia[[,]] and aqueous ammonia~~, and an aqueous solution of ammonium fluoride~~ to the cleaning liquid intermittently ~~with lapse of time~~ during the cleaning step ~~said cleaning liquid is used~~.

Claim 2 (withdrawn) The substrate cleaning method according to Claim 1, further comprising the step of measuring characteristics of said cleaning liquid, wherein a kind and an amount of said replenishing liquid are determined in response to a result of the measurement of said cleaning liquid.

Claim 3 (currently amended) The substrate cleaning method according to Claim 2, wherein, in the measuring step, hydrofluoric acid concentration is measured at a predetermined time interval and ~~water~~ aqueous ammonia is fed as said replenishing liquid so that a measurement value of said concentration falls within a predetermined range.

Claim 4 (withdrawn) The substrate cleaning method according to Claim 2, wherein said characteristics of said cleaning liquid is measured by at least one measurement selected from the group consisting of measurements of an absorbance at a predetermined wavelength, an infrared absorption spectrum, an ultraviolet absorption spectrum, an index of refraction, a specific gravity, a transmittance, and an electric conductivity, a measurement by means of a moisture titrator, and a measurement by means of a liquid (ion) chromatography.

Claim 5 (withdrawn) The substrate cleaning method according to Claim 3, wherein said hydrofluoric acid concentration of said cleaning liquid is measured by at least one measurement selected from the group consisting of measurements of an absorbance at a predetermined wavelength, an infrared absorption spectrum, an ultraviolet absorption spectrum, an index of refraction, a specific gravity, a transmittance, and an electric conductivity, a measurement by means of a moisture titrator, and a measurement by means of liquid (ion) chromotrography.

Claim 6 (currently amended) A substrate cleaning apparatus for cleaning a substrate, comprising:

a substrate cleaning bath containing therein a substrate cleaning liquid comprising at least one liquid selected from ~~the~~ a first group consisting of an aqueous solution of ammonium fluoride[[,]] and a mixture of an aqueous solution of ammonium fluoride and hydrofluoric acid; ~~and~~

a fluid source comprising at least one fluid selected from a second group consisting of ammonia and aqueous ammonia; and

~~liquid~~ fluid feeding means for feeding ~~a liquid~~ the fluid from said fluid source to said substrate cleaning bath ~~comprising at least one selected from the group consisting of ammonia and aqueous ammonia~~.

Claim 7 (currently amended) The substrate cleaning apparatus according to Claim 6, further comprising:

measuring means for measuring characteristics of said cleaning liquid in said substrate cleaning bath; and

control means for arithmetically processing a signal from said measuring means to control the feeding of the ~~liquid~~ fluid from said ~~liquid~~ fluid source ~~feeding means~~ to substrate cleaning bath by way of said fluid feeding means.

Claim 8 (original) The substrate cleaning apparatus according to Claim 7, wherein said measuring means comprises means for measuring at least one wavelength characteristic selected from the group consisting of an absorbance at a

predetermined wavelength, an infrared absorption spectrum, an ultraviolet absorption spectrum, and an index of refraction.

Claim 9 (withdrawn) The substrate cleaning apparatus according to Claim 7, wherein said measuring means comprises means for measuring at least one physical value selected from the group consisting of a specific gravity and a transmittance.

Claim 10 (withdrawn) The substrate cleaning apparatus according to Claim 7, wherein said measuring means comprises means for measuring an electric conductivity.

Claim 11 (withdrawn) The substrate cleaning apparatus according to Claim 7, wherein said measuring means comprises at least one measurement means selected from the group consisting of a moisture titrator and liquid (ion) chromatography.

Claim 12 (original) The substrate cleaning apparatus according to Claim 7, wherein said measuring means measures hydrofluoric acid concentration of said cleaning liquid.

Claim 13 (original) The substrate cleaning apparatus according to Claim 12, wherein said measuring means comprises means for measuring at least one wavelength characteristic selected from the group consisting of an absorbance at a predetermined wavelength, an infrared absorption spectrum, an ultraviolet absorption spectrum, and an index of refraction.

Claim 14 (withdrawn) The substrate cleaning apparatus according to Claim 12, wherein said measuring means comprises means for measuring at least one physical value selected from the group consisting of a specific gravity and a transmittance.

Claim 15 (withdrawn) The substrate cleaning apparatus according to Claim 12, wherein said measuring means comprises means for measuring an electric conductivity.

Claim 16 (withdrawn) The substrate cleaning apparatus according to Claim 12, wherein said measuring means comprises at least one measurement means selected from the group consisting of a moisture titrator and liquid (ion) chromatography.

Claim 17 (withdrawn) A substrate cleaning apparatus for cleaning a substrate, comprising:

a substrate cleaning bath containing therein a substrate cleaning liquid comprising at least one liquid selected from the group consisting of an aqueous solution of ammonium fluoride, and a mixture of an aqueous solution of ammonium fluoride and hydrofluoric acid; and

gas feeding means for feeding gas comprising at least ammonia.